Inventor: Yongjun Jeff Hu

Title: Methods of Forming Metal Silicide, and Semiconductor Constructions Comoprising Metal Silicide

Assignee: Micron Technology, Inc.

EV317136155

INFORMATION DISCLOSURE STATEMENT

PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, the Examiner's attention is directed to the references listed on the attached Form PTO-1449 and copies of which are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Date: June 26, 2003

Attorney: _____
David G. Latweesen, Ph.D.
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EV317136155

Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. MI22-2266	SERIAL NO. Filed herewith
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT Micron Technology, Inc.	
		FILING DATE Filed herewith	GROUP

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,187,679	2/13/01	Cabral, Jr. Et al.			
	AB	6,362,086	3/26/02	Weimer et al.			
	AC	5,852,319	12/22/98	Kim et al.			
	AD	5,997,634	12/7/99	Sandhu et al.			
	AE	6,090,708	7/18/00	Sandhu et al.			
	AF	6,306,766	10/23/01	Sandhu et al.			
	AG						
	AH						
	AI						
	AJ						

FOREIGN PATENT DOCUMENTS

		Document *Number*	Date	Country	Class	Subclass	Translation	
							Yes	No
	AK							
	AL							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

	AM		*"Mechanisms for enhanced C54-$TiSi_2$ formation in Ti-Ta alloy films on single-crystal Si"*, A. Quintero et al.; Journal of Materials Research; Vol. 14, No. 12 Dec. 1999 pp. 4690-4700
	AN		*"Enhanced formation of the C54 $TiSi_2$ by an interposed layer of molybdenum"*, A. Mouroux et al.; Appl. Phys. Lett. 69 (7), 12 August 1996; ©1996 American Institute of Physics
	AO		*"Low temperature formation of C54-$TiSi_2$ using titanium alloys"*, C. Cabral, Jr. Et al; Appl./ Phys. Lett. 71 (24) 15 December 1997 ©1997 American Institute of Physics; pp. 3531-3533
	AP		

EXAMINER	DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.